

**Appln No. 10/815,526**  
**Amdt date April 9, 2008**  
**Reply to Office action of December 26, 2007**

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Currently Amended) Process for forming a protective coating containing aluminium on the surface of a metal substrate in which the [[said]] substrate and a non-gaseous precursor containing aluminium are placed in contact, at a [[high]] treatment temperature sufficient for stoichiometric coating, with an atmosphere containing an active gas which reacts with the precursor to form a gaseous aluminium compound which decomposes on contact with the substrate depositing aluminium metal thereon, characterised in that the [[said]] atmosphere contains a gaseous compound of a modifier metal which decomposes on contact with the substrate and deposits the [[said]] modifier metal thereon simultaneously with the deposition of aluminium, wherein the gaseous compound of the modifier metal is zirconium oxychloride.
2. (Canceled)
3. (Currently Amended) Process according to claim 1, in which the [[said]] active gas at least in part comprises the [[said]] gaseous compound.
4. (Currently Amended) Process according to claim 2, in which the [[said]] active gas at least in part comprises the [[said]] gaseous compound.
5. (Currently Amended) Process according to claim 3, in which the [[said]] active gas solely comprises the [[said]] gaseous compound.
6. (Currently Amended) Process according to claim 3, in which the [[said]] active gas also contains at least one ammonium compound.

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7. (Currently Amended) Process according to claim 1, in which the [[said]] active gas and/or the [[said]] gaseous compound are formed by the vaporisation of at least one substance which is solid at ambient temperature mixed with the [[said]] precursor.
8. (Original) Process according to claim 1, in which the substrate contains at least one element which combines with the aluminium to form an intermetallic compound within the coating in which the aluminium is partly substituted by the modifier metal.
9. (Currently Amended) Process according to claim 8, in which the [[said]] element of the substrate is nickel and the [[said]] intermetallic compound is  $\beta$ -NiAl.
10. (Original) Process according to claim 1, in which the substrate is a nickel-based superalloy.
11. (Currently Amended) Process according to claim 1, in which the [[said]] active gas and/or the [[said]] gaseous compound contain at least one halogen.
12. (Canceled)
13. (Currently Amended) Process according to claim 11, in which the [[said]] active gas contains at least one compound selected from  $\text{NH}_4\text{Cl}$ ,  $\text{NH}_4\text{F}$  and  $\text{NH}_4\text{F}$ ,  $\text{HF}$ .
14. (Currently Amended) Process according to claim 12, in which the [[said]] active gas contains at least one compound selected from  $\text{NH}_4\text{Cl}$ ,  $\text{NH}_4\text{F}$  and  $\text{NH}_4\text{F}$ ,  $\text{HF}$ .
15. (Currently Amended) Process according to claim 1, in which the [[said]] precursor is an alloy of aluminium and chromium.
16. (Original) Process according to claim 1, in which the substrate and the precursor are at a distance from each other.

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17. (Original) Process according to claim 16, in which the substrate is located above the precursor.
18. (Original) Process according to claim 1, in which the substrate and the precursor are in contact.
19. (Original) Process according to claim 1, in which the substrate and the precursor are located in an enclosure permitting only limited exchanges with the exterior.
20. (Currently Amended) Process according to claim 1, in which in addition to the active gas and the gaseous compound the [[said]] atmosphere comprises an inert or reducing gas.
21. (Currently Amended) Process according to claim 1, in which the modifier metal is present in the [[said]] protective coating in a concentration by mass of less than 0.5%.
22. (Currently Amended) Process according to claim 21, in which the [[said]] concentration by mass lies at or above 500 ppm and below 1000 ppm.
23. (Currently Amended) Process according to claim 1, in which the ~~said high~~ treatment temperature is about 1080°C.
24. (Currently Amended) A method for forming a protective coating containing aluminium on a surface of a metal substrate, the method comprising:
  - placing the metal substrate and a non-gaseous precursor containing aluminium in contact, at a [[high]] treatment temperature sufficient for stoichiometric coating, with an atmosphere containing an active gas;
  - reacting the atmosphere containing the active gas with the non-gaseous precursor containing aluminium to form a gaseous aluminium compound;
  - decomposing the gaseous aluminum compound on contact with the metal substrate and depositing aluminium metal on the metal substrate, wherein the atmosphere further comprises a gaseous compound of a modifier metal; and

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decomposing the gaseous compound of the modifier metal on contact with the metal substrate and simultaneously depositing the modifier metal on the metal substrate with the depositing of the aluminium metal, wherein the gaseous compound of the modifier metal is zirconium oxychloride.

25. (Previously Presented) The method of claim 24, wherein the active gas consists of the gaseous compound of the modifier metal.